

### Abstract

The adoption of spectral flow cytometry and advancements in near-infrared (NIR) detection have increased the demand for additional fluorochromes. Leveraging the BD FACSDiscover™ A8 and S8 platforms' ability to detect signals up to 861 nm, BD recently introduced BD Horizon RealBlue™ 824 and RealViolet™ 828—two fluorochromes with emission maxima above 820 nm—and continues to expand possibilities on this wavelength range with BD Horizon RealYellow™ 825-P, BD Horizon RealRed™ 820-P, and BD Horizon RealUV 840-P (prototype names; final names pending), presented here for the first time.

Brightness and stability are critical for large-Stokes-shift fluorochromes emitting at long wavelengths. We show that the BD dyes >800 nm are bright and stable, demonstrating robust photo- and thermal stability. Each dye can be paired with its nearest neighbor (e.g., dyes in the 780 nm region), creating a new spectral position that can be added to existing multicolor panels to support higher plexity or used as an alternative to 780 nm dyes in smaller panels for improved peak separation. This approach reduces panel complexity scores and minimizes resolution loss caused by spillover spread from adjacent emissions.

### Introduction

Dye development in the NIR space has historically been challenging due to a variety of factors, including:

- Limitations of PMTs
- Instrument configurations
- Stability of NIR emitting dyes
- Broad emission curves for NIR emitting dyes

BD Horizon RealBlue™ 824 and RealViolet™ 828, as well prototypes BD Horizon RealYellow™ 825-P, BD Horizon RealRed™ 820-P, and BD Horizon™ RealUV 840-P, in conjunction with new instrument technology, overcome these challenges.

### Dye development methods

During our development process, dye prototypes are screened for sufficient brightness, clean spillover, as well as hardness. Hardness tests include photostability, thermal stability, and buffer compatibility. Dye prototypes that do not meet our standards are rejected. For dyes with emission maxima above 800 nm, due to the specific challenges of these positions, particular focus is placed on robust photo- (both pre- and post-staining) and thermal stability.

